## **PATENT APPLICATION**

Attorney Docket No.: 105192.01

**AMENDMENT TRANSMITTAL** 

OLIFF & BERRIDGE, PLC P.O. Box 19928 Alexandria, Virginia 22320 Telephone: (703) 836-6400 Facsimile: (703) 836-2787

In re the Application of

Koji SHIGEMATSU

Application No.: 09/722,506

Filed: November 28, 2000

For: PROJECTION OPTICAL SYSTEM AND EXPOSURE APPARATUS AND METHOD

Director of the U.S. Patent and Trademark Office Washington, D.C. 20231

Sir:

Transmitted herewith is an Amendment in the above-identified application.

- ☐ Entitlement to small entity status is hereby asserted.
- ☐ Small entity status of this application has been established.

The filing fee has been calculated as shown below:

	(Column 1)	(Column 2)	(Column 3)	
	CLAIMS REMAINING AFTER AMENDMENT	HIGHEST NO. PREVIOUSLY PAID FOR	PRESENT EXTRA	
TOTAL CLAIMS	*71 MINUS	**20	=51	
INDEP CLAIMS	*14 MINUS	***5	=9	
☐ FIRST PRESENTATION OF MULTIPLE DEP. CLAIM				

SMALL ENTITY			
RATE	ADD'L FEE		
x 9	\$		
x 40	\$		
+135	\$		
	\$		
•			

ADD'L FEE

x 18 \$ 918

x 80 \$ 720

+ 270 \$

\$1,638

<u>OR</u>

OTHER THAN A

- \* If the entry in Column 1 is less than the entry in Column 2, write "0" in Column 3.
- \*\* If the "Highest Number Previously Paid For" IN THIS SPACE is less than 20, write "20" in this space.
- \*\*\* If the "Highest Number Previously Paid For" IN THIS SPACE is less than 3, write "3" in this space.

The "Highest Number Previously Paid For" in this space (Total or Independent) is the highest number found from the equivalent box in Column 1 of a prior Amendment or the number of claims originally filed.

Check No. 117739 in the amount of \$1,638.00 is attached. The Director is hereby authorized to charge any other fees that may be required to complete this filing, or to credit any overpayment, to Deposit Account No. 15-0461. Two duplicate copies of this sheet are attached.

DEPOSIT ACCOUNT USE
AUTHORIZATION
Please grant any extension
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JAO:MAC/ccs

Date: April 2, 2001

Respectfully submitted,

James A. Oliff Registration No. 27,075

Mario A. Costantino Registration No. 33,565 

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105192.01

## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE to zeoo kal aook

In re the Application of

Koji SHIGEMATSU

Application No.: 09/722,506

Filed: November 28, 2000

PROJECTION OPTICAL SYSTEM AND EXPOSURE APPARATUS AND METHOD

Docket No.:

SECOND PRELIMINARY AMENDMENT

Director of the U.S. Patent and Trademark Office Washington, D. C. 20231

Sir:

For:

Prior to initial examination on the merits, please amend the above-identified application as follows:

## IN THE CLAIMS:

Please add the following claims 39-103:

A method of patterning a photosensitive workpiece with a pattern present on a reticle, the method comprising the steps of:

illuminating said reticle;

projecting light from said reticle with a projection optical system; and

exposing said photosensitive workpiece over an exposure field;

wherein said projection optical system comprises along an optical axis:

a first lens group having a positive power;

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